

C1
cont.
forming a photoresist pattern on the metal layer, such that a portion of the metal layer is exposed;

treating the exposed portion of the metal layer with a first plasma, prior to etching said photoresist pattern, and prior to etching said metal layer, using the photoresist pattern as a mask, to lower a binding force in the exposed portion; and

etching the treated portion of the metal layer to form a pixel electrode.

C2
13. (Amended) The method of claim 30, wherein the first gas is a reactive gas.

C3
17. (Amended) The method of claim 30, wherein the at least one second gas includes HBr plasma gas.

18. (Amended) The method of claim 30, wherein the at least one second gas includes a composition of HBr plasma gas and Cl₂ plasma gas.

19. (Amended) The method of claim 30, wherein the at least one second gas the at least one second gas [plasma] includes a composition of HBr plasma gas and CH₄ plasma gas.

C⁴

22. (Twice Amended) A method of patterning a metal layer, comprising:

depositing a metal layer over a substrate;

forming a mask on the metal layer, leaving a portion of the metal layer uncovered;

exposing the uncovered portion of the metal layer to a first plasma, prior to etching said mask, and prior to etching said metal layer, to lower a binding force in the uncovered portion; and

etching the uncovered portion of the metal layer with a second plasma to form a metal pattern.

Subj D2

C⁵

30. (Amended) A method of manufacturing a pixel electrode in a liquid crystal display device, comprising:

depositing a metal layer on a passivation layer which partially covers a transistor;

forming a photoresist pattern on the metal layer, leaving a portion of the metal layer uncovered;

exposing the uncovered portion of the metal layer to at least one first gas, prior to etching said photoresist pattern and prior to etching said metal layer, to lower a binding force in the uncovered portion; and

etching the uncovered portion of the metal layer with at least one second gas to form a pixel electrode.

Subj D3

Please add the following claims:

C6 --31. (New) A method of manufacturing a pixel electrode in a liquid crystal display device, comprising:

depositing a metal layer on a passivation layer which partially covers a transistor;

forming a photoresist pattern adjacent to the metal layer, leaving a portion of the metal layer uncovered;

exposing the uncovered portion of the metal layer to at least one first gas, prior to etching, to lower a binding force in the uncovered portion; and

etching the uncovered portion of the metal layer with at least one second gas to form a pixel electrode.--